

The Preparation of Triorganosilyl Derivatives of Hydroquinone, Resorcinol, Bisphenol-A and Terephthalic Acid

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In the course of the preparation of phenylene- and phthalate-siloxy copolymers with $-C_6H_4O-Si-$ and $-O_2CC_6H_4CO_2Si-$, di-triorganosilyl derivatives of hydroquinone and resorcinol, *1,4(1,3)-di-triorganosiloxy benzene* (R_3HQ and R_3RC), those of bisphenol-A (BPA), *2,2-bis-(4-triorganosiloxyphenyl)-propane* (R_3BPA), and terephthalic acid, *bis-triorganosilyl terephthalate* (R_3TPA) were isolated in pure states. R_3HQ and R_3RC were prepared from the reaction of triorganochlorosilane with the diphenols; R_3BPA , from the reaction of chlorosilane with BPA in the presence of aniline as a hydrogen chloride acceptor, or with the sodium salt of BPA in an inert solvent, and R_3TPA , from the reaction of chlorosilane with dipotassium

terephthalate. R_3TPA was found to be extremely sensitive towards solvolysis, while the phenolic silyl-ethers, the former three, were rather stable in both hydrolysis and alcoholysis.

Experimental

Triorganochlorosilanes.—A pure sample of trimethylchlorosilane (b. p. $58^\circ C$) was obtained from the Shinetsu Chemical Industrial Co. Dimethylbutylchlorosilane (b. p. $139-140^\circ C$), dimethylphenylchlorosilane (b. p. $76-78^\circ C/2$ mmHg) and diphenylmethylchlorosilane (b. p. $145-146^\circ C/2.5$ mmHg) were prepared by the Grignard route.¹⁾ Triphenylchlorosilane (m. p. $98-99^\circ C$) was isolated from high

1) T. Takiguchi and M. Abe, *J. Chem. Soc. Japan, Ind. Chem. Sec. (Kogyo Kagaku Zasshi)*, **66**, 625 (1963).

boiling residue²⁾ of the direct synthesis of phenylchlorosilanes. All the compounds were further purified by conventional methods just before use.

The Preparation of R_3HQ and R_3RC .—The general procedure will be described using 1,4-bis-trimethylsiloxy-benzene (Me_3HQ) as an example. A mixed sample of hydroquinone (33 g., 0.3 mol.) and trimethylchlorosilane (54 g., 0.5 mol.) was refluxed until the hydroquinone dissolved completely to give a clear yellow solution. The resultant solution was evaporated to remove the excess chlorosilan and then distilled under a vacuum. The distillate at 107–110°C/4 mmHg was a viscous liquid which solidified on standing. Recrystallization from ether gave 59 g. (77%) of pure Me_3HQ (m. p. 48°C) (lit. m. p. 46°C,³⁾ 52°C,⁴⁾ 48.9–49.3°C⁵⁾; b. p. 239°C (lit. b. p. 252°C,⁶⁾ 246°C³⁾). The following disilyl ethers of the diphenols were obtained by a very similar procedure: Me_3RC , b. p. 235–236°C, 92–93°C/2 mmHg (lit. b. p. 239°C,⁶⁾ 243°C⁴⁾, 237–240°C,⁷⁾ 116°C/7 mmHg³⁾; n_D^{20} 1.4755; d_4^{20} 0.947. Me_2BuHQ , b. p. 158–195°C/1.5 mmHg; n_D^{20} 1.4765; d_4^{20} 0.925. Me_2BuRC , b. p. 161–162°C/3 mmHg; n_D^{20} 1.4798; d_4^{20} 0.923. Me_2PhHQ , b. p. 137–139°C/0.5 mmHg; n_D^{20} 1.5720; d_4^{20} 1.087. $MePh_2HQ$, b. p. 237–238°C/0.5 mmHg; n_D^{20} 1.5882; d_4^{20} 1.113. Ph_3HQ , m. p. 225–226°C (lit. m. p. 215.8–216.0°C⁵⁾). (Ph_3HQ was prepared from the reaction in aniline.)

$Me_3HQ(RC)$.—Found: Si, 21.0 (21.7); mol. wt., 238 (244) (in benzene); MR_D^{20} — (75.35). Calcd. for $C_{12}H_{22}O_2Si_2$: Si, 22.0%; mol. wt., 254; MR_D , 74.38.

$Me_2BuHQ(RC)$.—Found: Si, 16.4 (16.0); mol. wt., 318 (326); MR_D , 104.7 (104.3). Calcd. for $C_{18}H_{34}O_2Si_2$: Si, 16.6%; mol. wt., 339; MR_D , 104.7. Me_2PhHQ .—Found: Si, 14.5; mol. wt., 377, 373; MR_D , 111.4. Calcd. for $C_{22}H_{26}O_2Si_2$: Si, 14.8%; mol. wt., 379; MR_D , 112.7.

$MePh_2HQ$.—Found: Si, 10.7; mol. wt., 491; MR_D , 152.2. Calcd. for $C_{22}H_{30}O_2Si_2$: Si, 11.2%; mol. wt., 503; MR_D , 150.9.

Ph_3HQ .—Found: Si, 8.2; mol. wt., 633 (1,4-dioxane). Calcd. for $C_{12}H_{14}O_2Si_2$: Si, 8.9%; mol. wt., 627.

R_3HQ was fairly stable in hydrolysis; e. g., Me_3HQ recovered unchanged even after 2 hr.' boiling with distilled water. R_3RC was less stable than R_3HQ . However, both were hydrolyzed gradually by prolonged heating with 1/20 N sulfuric acid, yielding the diphenols and the corresponding disiloxanes. The products were also characterized by their infrared absorption spectra.⁹⁾ X-Ray powder patterns for crystalline ethers are given below:

Me_3HQ

d, kX :	11.05	5.57	5.31	4.93	4.42	3.90	3.71
	3.47	3.04					
I/I_0 :	1.00	0.39	0.29	0.14	0.24	0.29	0.26
	0.14	0.13					

Ph_3HQ

d, kX :	12.26	8.51	7.76	6.92	6.15	4.70	4.53
	4.37	4.17	4.02	3.59	3.48	3.39	
I/I_0 :	0.19	0.45	0.36	0.28	0.93	1.00	0.48
	0.98	0.63	0.36	0.26	0.24	0.25	

The Preparation of R_3BPA .—A typical procedure will be detailed for 2,2-bis-(4-dimethylphenylsiloxy-phenyl)-propane (Me_2PhBPA). A mixture of BPA (46 g., 0.2 mol.) and dimethylphenylchlorosilane (85 g., 0.5 mol.) was refluxed for 5 hr. After it had then been cooled to room temperature, a solution of aniline (37 g., 0.4 mol.) in 300 ml. of ether was vigorously stirred into the mixture, after which the mixture was refluxed for an additional 2 hr. The resultant solution was filtered to remove aniline hydrochloride and concentrated to a clear viscous liquid, from which crude Me_2PhBPA boiling at 266–285°C (1.5 mmHg) was obtained by distillation. The redistillation of the fraction gave 74 g. (74%) of pure Me_2PhBPA ; b. p. 286–287°C/1.5 mmHg, n_D^{20} 1.5746, d_4^{20} 1.117.

It was found that the use of aniline as a hydrogen chloride acceptor was essential for the successful preparation; otherwise, the reaction was not completed, it was always accompanied by the formation of considerable amounts of mono-silyl ether, and the yield of bis-silyl ether was less than 40%.

In another preparation, an ethereal solution of dimethylphenylchlorosilane (85 g., 0.5 mol.) was added to a stirred slurry of sodium salt of BPA (54 g., 0.2 mol.) in ether. After it has been stirred for 2 hr. under refluxing, the mixture was filtered to remove sodium chloride; then the filtrate was evaporated to give an oily viscous liquid, which gave 66 g. (66%) of Me_2PhBPA by fractionation under a vacuum. The following were obtained analogously in a consistent yield of 65–70%. Me_3BPA , b. p. 179–180°C/1.5 mmHg, n_D^{20} 1.5178, d_4^{20} 0.981; Me_2BuBPA , b. p. 211–214°C/1.5 mmHg, n_D^{20} 1.5102, d_4^{20} 0.976; and $MePh_2BPA$, b. p. 297–300°C/0.5 mmHg, n_D^{20} 1.5777, d_4^{20} 1.084.

Triphenylchlorosilane was found to be much less reactive to BPA than the other chlorosilanes. Therefore, a reaction in a high boiling solvent (toluene, xylene, etc.) using aluminum chloride as a catalyst was necessary; otherwise, the yield of bis-silyl ether always remained below 20%. Ph_3BPA was a fine crystalline substance melting at 151–152°C; it was obtained in a 47% (mean) yield by preparation in xylene. It was readily soluble in benzene, toluene and xylene, and insoluble in hexane, acetone, ethanol and methanol.

X-Ray powder diffraction data of Ph_3BPA :

d, kX :	8.93	7.48	6.86	6.42	5.83	5.28	5.19
	4.80	4.60	4.51	4.33	3.87	3.68	
I/I_0 :	0.47	0.25	0.43	0.23	0.48	0.38	0.37
	0.31	0.55	0.73	1.00	0.22	0.38	

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Me₂PhBPA.—Found: Si, 11.0; mol. wt., 506 (benzene); MR_D, 147.0. Calcd. for C₃₁H₃₆O₂Si₂: Si, 11.3%; mol. wt., 497; MR_D, 146.9.

Me₃BPA.—Found: Si, 14.7; mol. wt., 366; MR_D, 115.2. Calcd. for C₂₇H₃₂O₂Si₂: Si, 15.1%; mol. wt., 373; MR_D, 112.0.

Me₂BuBPA.—Found: Si, 11.9; mol. wt., 455; MR_D, 140.1. Calcd. for C₂₇H₄₄O₂Si₂: Si, 12.3%; mol. wt., 457; MR_D, 139.8.

MePh₂BPA.—Found: Si, 8.83; mol. wt., 617; MR_D, 191.3. Calcd. for C₄₁H₄₀O₂Si₂: Si, 9.1%; mol. wt., 621; MR_D, 188.5.

Ph₃BPA.—Found: Si, 7.1; mol. wt., 750. Calcd. for C₃₁H₄₄O₂Si₂: Si, 7.5%; mol. wt., 745.

The identifications of these bis-silyl ethers were further established by their hydrolytic cleavage. The hydrolysis of Me₂BuBPA (22.8 g., 0.05 mol.) with 1/20 N sulfuric acid by refluxing it for 10 hr. afforded BPA (10.0 g., 0.044 mol.) and 1,3-dibutyltetramethyldisiloxane (b. p. 207–208°C; 11.3 g., 0.046 mol.). Infrared absorption data⁹⁾ were also recorded.

Throughout the infrared absorption spectra of all silyl ethers (R₃BPA, R₃HQ and R₃RC), a very strong and characteristic absorption band in the 910–925 cm⁻¹ region was found to exist. Its assignment still remains uncertain; however, it is very probably due to the existence of phenylene- or phenyl-silyl ether bonding (–C₆H₄–O–Si– or C₆H₅–O–Si–) in these compounds. An entire absence of the band in BPA, diphenols and in phenol, and its appearance in the silyl derivatives of BPA, in diphenols and in all phenoxysilanes¹⁰⁾ seems to support this assignment strongly.

Bis-triphenylsilyl Terephthalate.—In a manner similar to that employed for R₃TPA (R₃=Me₃, Me₃Bu, Me₂Ph and MePh₂) in the preceding paper,¹¹⁾ bis-triphenylsilyl terephthalate (Ph₃TPA) was obtained in 67% yield from the reaction of dipotassium terephthalate with triphenylchlorosilane in boiling toluene.

Ph₃TPA was a fine acicular crystal melting at 242–243°C, hardly soluble in ordinary solvents at room temperature, and fairly soluble in boiling toluene, xylene, dioxane and chlorobenzene.

Found: Si, 7.7; mol. wt., 688, 692 (Rast method). Calcd. for C₄₄H₃₄O₄Si₂: Si, 8.2%; mol. wt., 683.

X-Ray powder diffraction data of Ph₃TPA:

<i>d</i> , kX:	8.93	7.83	7.31	7.28	5.79	5.13	5.10
	4.75	4.57	4.15	4.02			
<i>I</i> / <i>I</i> ₀ :	0.28	0.18	0.13	0.11	0.12	0.62	0.19
	0.39	1.00	0.34	0.21			

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